

What is claimed is:

1. (currently amended) An apparatus for measuring viscosity of a medium with a micromechanical measuring facility and electronic systems for measuring, transducing, and analyzing signals, with the following features:

a measuring zone implemented integrated on a mechanically stable substrate is freely accessible or enclosed within a measuring chamber with pores or openings for diffusive or convective mass transport, the measuring zone containing two or several more closely spaced conductors of which at least one is connected to a controllable current source or HF voltage source and of which at least one is completely or partially cantilevered within from a suspension into the measuring zone, the position of the cantilevered conductor(s) being defined within the measuring zone by the resiliency of the bracket suspension or their/its own inherent resiliency and by voltage-dependent, or current-dependent electrical or magnetic attraction, or repelling forces, which can be changed by means of said HF voltage sources source or current sources source, and the measuring zone containing an implemented integrated measuring device set-up for detection of the detecting a viscosity-dependent change in position change of the conductor(s) in response to changes of said attraction or repelling forces.

2. (currently amended) The apparatus of claim 1, wherein the substrate consists of comprises a semiconductor material and contains implemented integrated circuits for detecting the position respectively or change in position change of the cantilevered movable conductor(s), and/or for the signal transduction, and/or the signal export, and/or for the controllable current or HF voltage sources.

3. (currently amended) The apparatus of claim 1, wherein a tightly implemented an integrated loop or flat coil and [[a]] the cantilevered movable conductor conductor(s) forming a loop are arranged on the substrate at the place of the measuring zone, this the cantilevered movable conductor conductor(s) being fixed to suspended from the substrate at two or more points within the measuring zone.

4. (currently amended) The apparatus of claim 1, wherein the substrate is formed as a bar-shaped, thin tip at ~~the~~ place of the measuring zone.

5. (currently amended) The apparatus of claim 4, wherein the measuring zone is ~~connected with the outer medium separated from the medium to be analyzed by~~ a dialysis membrane, ~~the resulting forming~~ a measuring chamber ~~being~~ filled with a macromolecular sensitive fluid, the components of which cannot penetrate the dialysis membrane and the viscosity of which is determined by reversible affinity bonds between polymer substances and can be changed by the concentration of one or several more analyte molecules for which the dialysis membrane is permeable, wherein ~~at any point the maximum spacing between~~ the sensitive fluid volume ~~being bordered confined~~ by the dialysis membrane and the substrate is ~~not remote from the dialysis membrane by more than .5 mm.~~

6. (currently amended) The apparatus of claim 5, wherein the bar-shaped, thin tip with the measuring zone is ~~positioned arranged in and partially fills~~ the lumen of a dialysis hollow fiber, ~~but not completely filling out this lumen, so that for forming a measuring chamber in the region between hollow fiber membrane and substrate acts as a measuring chamber.~~

7. (currently amended) The apparatus of claim 6, wherein the ~~movable cantilevered~~ conductor(s) which is (are) cantilevered in the measuring zone consist(s) of thin metal wires and wherein the resilient resistance of the ~~movable~~ conductor(s) against the field-induced force is mainly based on the torsion of said wires.

8. (currently amended) The apparatus of claim 7, wherein the cantilevered ~~movable~~ conductor(s) are is/are arranged in the field of a permanent magnet in such a way, that this field is directed perpendicularly to the ~~movable~~ conductor(s) and to their/its main direction of movement and wherein the ~~movable~~ conductors are conductor(s) is/are connected to a controllable current source.

9. (currently amended) A method of measuring viscosity with a device according to claim 8, wherein the position change in the position of the cantilevered movable conductor(s) referring relative to the substrate or one other another conductor being is induced by a change of the electrical HF field or of the magnetic field intensity and the viscosity dependent velocity or extent of this change in position induced change being established by means of a preferably high frequency capacity or impedance measurement or by means of the a frequency-shift of an HF-oscillator.

10. (currently amended) The method of measuring viscosity of claim 9, wherein the viscosity-dependent amplitude of the measured position change in position of the cantilevered movable conductor(s) is evaluated at a suitable modulation or switching frequency of the HF field affecting the conductors conductor(s) or of the current flowing in the conductor(s) or as a function of the modulation or switching frequency.

11. (currently amended) The method of measuring viscosity of claim 9, wherein the intensity strength or direction of the magnetic force or the intensity strength of the electrostatic force acting on to the cantilevered movable conductor(s) [[is]] is/are abruptly changed by the control of the current- or HF voltage source, source(s) and subsequently, the viscosity-dependent position change in position of the conductors is/are measured as a function of time.

12. (currently amended) A method of making a device for measuring viscosity according to claims claim 8, wherein after completion of all active and passive components of the viscosity sensor measuring device on a suitable semiconductor substrate, [[() including the implemented leading paths integrated conductors.[[()]] but before separation of the chips jointly generated on the semiconductor substrate (wafer), an additional photolithographically structured soft resist mask is applied to enable for a localized isotropic insulator isotropic insulation etching process on the parts of the upper conducting path uppermost conductor layer being provided in the completed sensor as for forming the cantilevered movable conductors and wherein these the parts of the upper

conducting path uppermost conductor layer are undercut by etching and completely separated from the corresponding sections of the an insulating base in by the localized isotropic insulator isotropic insulation etching process.

13. (currently amended) The method of claim 12, wherein the a layer intermediate layer between the uppermost conductor path layer and the a lower conductor is dielectric and consists of at least two layers of different chemical compounds, and wherein the lower part of the interlayer intermediate layer is not affected by immune from the etching process agent used for the isotropic undercutting of the upper conductor path.

14. (currently amended) The method of claim 13, wherein the upper partial layer part of the intermediate layer consists of silicon dioxide or silicate glass and one of the lower partial layers consists of  $\text{Si}_3\text{N}_4$ .

15. (currently amended) An apparatus for measuring the viscosity of a fluid, comprising:

a substantially rigid support;  
an extension protruding from the support and provided with a first conductive path;

a cantilever member comprising a second conductive path extending over the first conductive path and resiliently biased to a first position spaced therefrom;

means for cyclically energizing at least one of the first and second conductive paths for moving the cantilever member to a second position; and

means for detecting the rate of return of the cantilever member to its first position to derive a value representative of the viscosity.

16. (original) The apparatus of claim 15, wherein the length and width of the extension are about 1 mm and 300  $\mu\text{m}$ , respectively.

17. (original) The apparatus of claim 16, wherein the extension and the

cantilever member are mounted in a chamber formed by a membrane of predetermined permeability.

18. (original) The apparatus of claim 17, wherein the membrane is a dialysis membrane and wherein the layout of the chamber is such that the distance between any point in the chamber and a permeable portion of the membrane does not exceed .3 mm.

19. (original) The apparatus of claim 18, wherein the dialysis membrane has a molecular weight cut-off of about 10 kDa.

20. (original) The apparatus of claim 19, wherein the chamber contains lyophilized components of a fluid sensitive to glucose.

21. (currently amended) The apparatus of claim 15, wherein the at least one of the first and second conductive paths is adapted to be energized by direct current.

22. (currently amended) The apparatus of claim 15, wherein the at least one of the first and second conductive paths is adapted to be energized by high frequency voltage.

23. (original) The apparatus of claim 22, wherein the high frequency voltage is in the Ghz range.

24. (currently amended) A method of measuring the viscosity of a fluid, comprising the steps of:

providing a substantially rigid member with a first conductive path therein;  
providing a resiliently flexible member having a second conductive path therein biased into a first position spaced from the first conductive path;  
subjecting the rigid and flexible members to the fluid;  
energizing at least one of the first and second conductive paths to move the

flexible member to a second position; and

measuring the rate of movement of the flexible member to derive therefrom a value representative of the viscosity.

25. (currently amended) The method of claim 24, wherein the at least one conductive path is energized by high frequency voltage and wherein the rate of movement is measured by the capacitance between the first and second conductive paths.

26. (currently amended) The method of claim 24, wherein the at least one conductive path is energized by direct current and wherein the rate of movement is measured by rate of relaxation of the resilient member.

27. (original) The method of claim 24, wherein the rigid and resiliently flexible members are disposed in a measuring chamber formed by a membrane of predetermined permeability and wherein the chamber further contains a fluid sensitive to the fluid for measuring the viscosity thereof by affinity.

28. (currently amended) A method of fabricating an apparatus for measuring the viscosity of a fluid, comprising an elongate rigid member extending from a substrate of a semiconductor material for supporting a first conductive path and a second member supporting a second conductive path and mounted for oscillations movements relative to the first member, wherein the second member is formed by depositing on the parts of the substrate provided with the second conductive path an additional photolithographic lacquer resist mask for undercutting by localized isotropic insulator etching.

29. (original) The method of claim 28, wherein an intermediate layer comprising at least two superposed layers of different chemical compounds is provided between the first and second conductive paths and wherein the etching step is performed on an upper one of the layers.

30. (original) The method of claim 29, wherein the etching step is performed with an etching agent removing layers of one of silicon dioxide and silicate glass and immune to lower layers of  $\text{Si}_3\text{N}_4$ .

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